

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

David S. Pecora

Serial No.: Not Assigned

Filed: Concurrently Herewith (May 11, 2001)

For: ETCH OF SILICON NITRIDE SELECTIVE
TO SILICON AND SILICON DIOXIDE USEFUL
DURING THE FORMATION OF A
SEMICONDUCTOR DEVICE

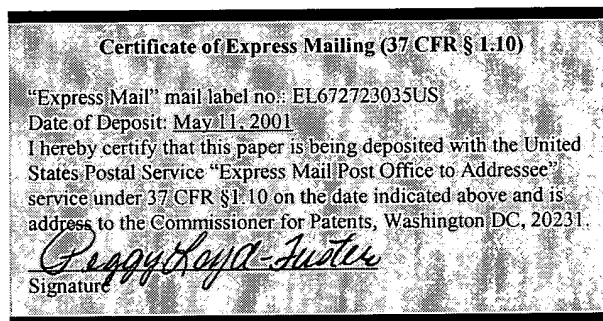
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§ Group Art Unit: Not Assigned
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§ Examiner: Not Assigned
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§ Atty. Docket: 00-0737.00
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INFORMATION DISCLOSURE STATEMENT

Box Patent Application
Commissioner for Patents
Washington, D.C. 20231

Dear Sir:



In compliance with the duty of disclosure under 37 CFR § 1.56, Applicant respectfully requests that this Information Disclosure Statement be entered and that the references listed on the attached Form PTO-1449 be considered by the Examiner and made of record. A copy of the listed reference is enclosed for the convenience of the Examiner.

In accordance with 37 CFR § 1.97(b), this Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other possible material information as defined in 37 CFR § 1.56(a) exists.

The following reference is submitted for the Examiner's review:

Related Art:

"Highly Selective Etching of Silicon Nitride Over Silicon and Silicon Dioxide," J. Vac. Sci. Technol. A 17(6), Nov/Dec 1999

As this information is being submitted before a first office action on the merits, Applicant understands that no fee or certification is required for the submission and consideration of this information at this time.

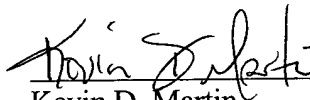
If there are any matters which may be resolved or clarified through telephone interview, the Examiner is respectfully requested to contact Applicant's undersigned attorney at the number indicated.

* * * *

A Form PTO-1449 is enclosed herewith.

Respectfully submitted,

Date: 11-May-01


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Agent for Applicant

FORM: PTO-1449 (REV: 7-80)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	Atty Docket No: 00-0737.00/US	Serial No: Not Assigned
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (37 CFR 1.98(b)) (use several sheets if necessary)		Applicant: David S. Pecora	
		Filing Date: Concurrently Herewith (May 11, 2001)	Group: Not Assigned

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	
	AA					
	AB					
	AC					
	AD					
	AE					
	AF					
	AG					
	AH					
	AI					
	AJ					
	AK					

11002 U.S. PTO
09/854206
05/11/01

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
	AL					Yes	No
	AM					<input type="checkbox"/>	<input type="checkbox"/>
	AN					<input type="checkbox"/>	<input type="checkbox"/>
	AO					<input type="checkbox"/>	<input type="checkbox"/>
	AP					<input type="checkbox"/>	<input type="checkbox"/>
	AQ					<input type="checkbox"/>	<input type="checkbox"/>

Initial

OTHER ART (including author, title, date, pertinent pages, etc.)

	AR		"Highly Selective Etching of Silicon Nitride Over Silicon and Silicon Dioxide," J. Vac. Sci. Technol. A 17(6), Nov/Dec 1999
	AS		
	AT		
	AU		

Examiner:	Date Considered:
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication with applicant.